

Joint International Conference on The 8th ICMAP & The 9th ISFM

January 17-20, 2021 | Online Conference

[TC3] Plasma Deposition and Etching - I (PECVD, Beam, Tilting, Pulsing)	
Date / Time	January 19 (Tue.), 2021 / 14:30-16:00
Place	Channel C
Session Chair(s)	Ho Jun Kim (Gachon Univ., Korea) Kazufumi Hata (Kanazawa Univ., Japan)

[TC3-1] Invited

14:30-15:00

Open-Air Plasma-Enhanced Deposition of Titanium Oxide Thin Films

Rodolphe Mauchauffé, Jongwoon Kim, Donghyun Kim, and Se Youn Moon

Jeonbuk Nat'l Univ., Korea

[TC3-2]

15:00-15:20

Interactions of Si and SiO₂ Surfaces with Energetic SiF_x⁺ and SiCl_x⁺ Ion Beams

Abdullah Jaber, Michiro Isobe, Tomoko Ito, Kazuhiro Karahashi, and Satoshi Hamaguchi

Osaka Univ., Japan

[TC3-3]

15:20-15:40

Investigation of Plasma Distribution Dependency on Pattern Tilting in 300mm VHF-CCP Si Etch

Seongjae Lim, Jaemin Song, Taejun Park, Haneul Lee, Sung Hyun Son, and Gon-Ho Kim

Seoul Nat'l Univ., Korea

[TC3-4]

15:40-16:00

Etch Characteristics of Nanoscale Poly-Si Fins by Using Pulsed Ar / Cl₂ Inductively Coupled Plasmas

Hee Ju Kim, Geun Young Yeom, Ji Soo Oh, Jong Woo Hong, Gyo Wun Kim, Won Jun Jang, Jeong Wan Kim, Chae Lin Lee, and Dong Woo Kim

Sungkyunkwan Univ., Korea